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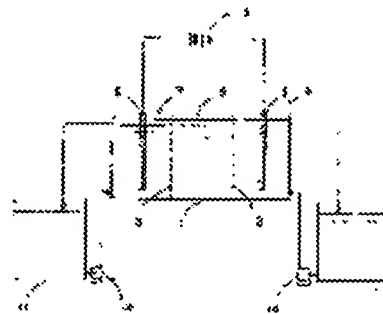
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(54) ADJUSTMENT OF METAL ION CONCENTRATION IN NICKEL PLATING LIQUOR

(57)Abstract:

PURPOSE: To control the metal ion concentration of nickel plating liquor as well as reuse electrodeposited metal as anodic material by the procedure in which a plating liquor whose metal ion concentration is enriched is electrolysed in the cathode compartment of a three-compartment type diaphragmatic electrolytic bath to deposit metal on the cathodic electrode and at the same time the cathodic liquor whose metal ion concentration is lowered is used for adjusting the concentration of plating liquor.

CONSTITUTION: Upon electrifying the electrolytic bath 1 from the DC power source 13, metal ion is deposited on the cathode 5 in the metallic form in the cathode compartment and also SO_4^{2-} and Cl^- pass through the anion exchange membrane 2 into the intermediate compartment 6. In the anode 8, O_2 gas is given off and H^+ and Na^+ pass through the cation exchange membrane 3 into the intermediate compartment 6. When Ni ion concentration in the cathode compartment is reduced to approx. 20 to 30 g/l as electrolysis exceeds, the metal ion concentration of plating liquor can be adjusted by repeatedly making a batchwise operation to return cathodic liquor to plating tank. The metal recovered is reused as anodic material.



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